



PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Andreas et al.

Serial No.: 10/645,710

Filed: August 21, 2003

For: WAFER CLEANING METHOD AND
RESULTING WAFER

Confirmation No.: 8457

Examiner: Tu Tu V. Ho

Group Art Unit: 2818

Attorney Docket No.: 2269-5663US
(02-1325.00/US)

Notice of Allowance Mailed:

January 26, 2005

CERTIFICATE OF MAILING

I hereby certify that this correspondence along with any attachments referred to or identified as being attached or enclosed is being deposited with the United States Postal Service as First Class Mail on the date of deposit shown below with sufficient postage and in an envelope addressed to the Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.

February 25, 2005
Date

Leah J. Barrow
Signature

Leah J. Barrow
Name (Type/Print)

AMENDMENT PURSUANT TO 37 C.F.R. § 1.312(a)

Mail Stop ISSUE FEE
Commissioner for Patents
P.O. Box 1450
Alexandria, Virginia 22313-1450

Sir:

Please amend the above-referenced application as follows:

Amendments to the Specification begin on page 3 of this paper.

Please
Enter
06/22/05
TH



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COMMENTS ON STATEMENT OF REASONS FOR ALLOWANCE

Mail Stop Issue Fee
Commissioner for Patents
PO Box 1450
Alexandria, VA 22313-1450

Sir:

The Examiner indicates:

The prior art of record fails to teach or render obvious a method of cleaning a semiconductor wafer including at least one registration mark having all exclusive limitations as recited in claims 1, 19, and 30, comprising providing a semiconductor wafer comprising at least one registration mark and exposing the semiconductor wafer to a cleaning solution, the at least one registration mark comprising at least one trench having a trench width from approximately 1.0 μm to approximately 3.0 μm , the cleaning solution either comprising tetramethylammonium hydroxide and at least one surfactant, the at least one surfactant as recited in claims 1 and 19, or the cleaning solution consisting essentially of tetramethylammonium hydroxide and at least one surfactant, the at least one surfactant comprising at least one acetylenic diol surfactant.

noted-
06/22/05
TH